

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No.	:	10/595,660	Confirmation No. 4264
Applicant	:	Yuichiro Shindo	
371 Filed	:	May 3, 2006	
Art Unit	:	1793	
Examiner	:	Jessee Randall Roe	
Customer No.	:	00270	
Title	:	HIGH PURITY HAFNIUM, TARGET AND THIN FILM COMPRISING SAID HIGH PURITY HAFNIUM, AND METHOD FOR PRODUCING HIGH PURITY HAFNIUM	

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RESPONSE TO RESTRICTION REQUIREMENT

Sir:

This is a timely response to the written Restriction Requirement dated July 1, 2008.

Election

In the present application, Applicants elect without traverse to prosecute the invention directed to hafnium having a purity of 4N or higher. Thus, Group I is elected and includes claims 1 and 2.

Please charge any deficiency or credit any overpayment for entering this Response to our deposit account no. 08-3040.

Respectfully submitted,
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